United States of America United States Patent and Trademark Office

AFS

Reg. No. 5,975,022

Registered Feb. 04, 2020

Int. Cl.: 7, 9

Trademark

Principal Register

HORIBA STEC, Co., Ltd (JAPAN kabushiki kaisha (k.k.))

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CLASS 7: Machines and structural parts therefor for manufacturing semiconductors, solar cells, light-emitting diodes, displays, liquid crystal and organic electroluminescent elements; fluid controllers being structural parts of machines for manufacturing semiconductors, solar cells, light-emitting diodes, displays, liquid crystal and organic electroluminescent elements; fluid measurement apparatus being structural parts of machines for manufacturing semiconductors, solar cells, light-emitting diodes, displays, liquid crystal and organic electroluminescent elements; fluid flow controllers being structural parts of machines for manufacturing semiconductors, solar cells, light-emitting diodes, displays, liquid crystal and organic electroluminescent elements; fluid flow meters being structural parts of machines for manufacturing semiconductors, solar cells, light-emitting diodes, displays, liquid crystal and organic electroluminescent elements; fluid flow sensors being structural parts of machines for manufacturing semiconductors, solar cells, light-emitting diodes, displays, liquid crystal and organic electroluminescent elements; fluid distributors being structural parts of machines for manufacturing semiconductors, solar cells, light-emitting diodes, displays, liquid crystal and organic electroluminescent elements; fluid flow distributors being structural parts of machines for manufacturing semiconductors, solar cells, light-emitting diodes, displays, liquid crystal and organic electroluminescent elements; fluid flow ratio controllers being structural parts of machines for manufacturing semiconductors, solar cells, light-emitting diodes, displays, liquid crystal and organic electroluminescent elements; fluid velocity controllers being structural parts of machines for manufacturing semiconductors, solar cells, light-emitting diodes, displays, liquid crystal and organic electroluminescent elements; fluid velocity measurement apparatus being structural parts of machines for manufacturing semiconductors, solar cells, light-emitting diodes, displays, liquid crystal and organic electroluminescent elements; pressure controllers being structural parts of machines for manufacturing semiconductors, solar cells, light-emitting diodes, displays, liquid crystal and organic electroluminescent elements; pressure meters being structural parts of machines for manufacturing semiconductors, solar cells, light-emitting diodes, displays, liquid crystal and organic electroluminescent elements; pressure sensors being structural parts of machines for manufacturing semiconductors, solar cells, light-emitting diodes, displays, liquid crystal and organic electroluminescent elements; concentration controllers being structural parts of machines for manufacturing semiconductors, solar cells, light-emitting diodes, displays, liquid crystal and organic electroluminescent elements; concentration meters being structural parts of machines for manufacturing semiconductors, solar cells, light-emitting diodes, displays, liquid crystal and organic electroluminescent elements; concentration monitors being structural parts of machines for manufacturing semiconductors, solar cells, lightemitting diodes, displays, liquid crystal and organic electroluminescent elements; concentration sensors being structural parts of machines for manufacturing semiconductors, solar cells, light-emitting diodes, displays, liquid crystal and organic electroluminescent



Director of the United States Patent and Trademark Office



elements

CLASS 9: Measuring or testing machines and instruments, namely, technical measuring, testing and checking apparatus and instruments for measuring, testing and checking the quantity of fluid flow, fluid pressure, fluid concentration, gas concentration of gas and liquids; fluid flow controllers for use in controlling a gas concentration; fluid measurement apparatuses, namely, gas concentration meters; fluid flow controllers namely, automatic liquid-flow control machines and instruments for use in controlling a gas concentration; fluid flow meters; fluid flow sensors, namely, electronic sensors for measuring fluid flow; fluid distributors, namely, flow regulators for selecting and distributing multiple types of fluid to multiple supply lines; fluid flow distributors, namely, flow regulators for selecting and distributing the flow rate of fluid for supplying to multiple supply lines; fluid flow ratio controllers, namely, flow regulators for controlling the flow ratio of fluid for supplying to multiple supply lines; fluid flow controllers for regulating the flow velocity of liquids and gases; fluid velocity measurement apparatus; pressure controllers for controlling the pressure of liquid, semi-liquid, and gaseous substances in industrial processes; pressure meters, namely, pressure meter indicators for use in controlling a gas concentration; pressure sensors; concentration controllers, namely, electronic controllers for regulating liquid or gas concentration; concentration meters; laboratory apparatuses and instruments for use in measuring fluid flow, fluid pressure, fluid concentrations, or gas concentrations

THE MARK CONSISTS OF STANDARD CHARACTERS WITHOUT CLAIM TO ANY PARTICULAR FONT STYLE, SIZE OR COLOR

PRIORITY CLAIMED UNDER SEC. 44(D) ON JAPAN APPLICATION NO. 2018-087135, FILED 07-04-2018, REG. NO. 6163250, DATED 07-19-2019, EXPIRES 07-19-2029

SER. NO. 88-225,504, FILED 12-11-2018

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REQUIREMENTS TO MAINTAIN YOUR FEDERAL TRADEMARK REGISTRATION

WARNING: YOUR REGISTRATION WILL BE CANCELLED IF YOU DO NOT FILE THE DOCUMENTS BELOW DURING THE SPECIFIED TIME PERIODS.

Requirements in the First Ten Years* What and When to File:

- *First Filing Deadline:* You must file a Declaration of Use (or Excusable Nonuse) between the 5th and 6th years after the registration date. See 15 U.S.C. §§1058, 1141k. If the declaration is accepted, the registration will continue in force for the remainder of the ten-year period, calculated from the registration date, unless cancelled by an order of the Commissioner for Trademarks or a federal court.
- *Second Filing Deadline:* You must file a Declaration of Use (or Excusable Nonuse) and an Application for Renewal between the 9th and 10th years after the registration date.* See 15 U.S.C. §1059.

Requirements in Successive Ten-Year Periods* What and When to File:

• You must file a Declaration of Use (or Excusable Nonuse) and an Application for Renewal between every 9th and 10th-year period, calculated from the registration date.*

Grace Period Filings*

The above documents will be accepted as timely if filed within six months after the deadlines listed above with the payment of an additional fee.

*ATTENTION MADRID PROTOCOL REGISTRANTS: The holder of an international registration with an extension of protection to the United States under the Madrid Protocol must timely file the Declarations of Use (or Excusable Nonuse) referenced above directly with the United States Patent and Trademark Office (USPTO). The time periods for filing are based on the U.S. registration date (not the international registration date). The deadlines and grace periods for the Declarations of Use (or Excusable Nonuse) are identical to those for nationally issued registrations. See 15 U.S.C. §§1058, 1141k. However, owners of international registrations do not file renewal applications at the USPTO. Instead, the holder must file a renewal of the underlying international registration at the International Bureau of the World Intellectual Property Organization, under Article 7 of the Madrid Protocol, before the expiration of each ten-year term of protection, calculated from the date of the international registration. See 15 U.S.C. §1141j. For more information and renewal forms for the international registration, see http://www.wipo.int/madrid/en/.

NOTE: Fees and requirements for maintaining registrations are subject to change. Please check the USPTO website for further information. With the exception of renewal applications for registered extensions of protection, you can file the registration maintenance documents referenced above online at h ttp://www.uspto.gov.

NOTE: A courtesy e-mail reminder of USPTO maintenance filing deadlines will be sent to trademark owners/holders who authorize e-mail communication and maintain a current e-mail address with the USPTO. To ensure that e-mail is authorized and your address is current, please use the Trademark Electronic Application System (TEAS) Correspondence Address and Change of Owner Address Forms available at http://www.uspto.gov.

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